

AMENDMENTS TO THE CLAIMS

1. (Original) A method for fabricating a Fiber Bragg Grating element, comprising:

(a) providing a mask having a predetermined pattern and a wafer, wherein a light-guiding channel filled with light-guiding substance is formed on the wafer, and a photoresist layer is formed on the wafer;

(b) adjusting the magnification of a photolithography apparatus to a first Mag. and transferring the predetermined pattern on the mask to the photoresist layer on the wafer to form a first pattern; and

(c) removing the light-guiding substance not covered by the photoresist layer so that the first pattern is transferred to the light-guiding channel thus forming a Fiber Bragg Grating element, which picks out the light of a specific wavelength.

2. (Original) The method as claimed in claim 1, wherein the mask comprises a glass substrate.

3. (Original) The method as claimed in claim 1, wherein the predetermined pattern is made of Cr.

4. (Original) The method as claimed in claim 1, further comprising:

(d) adjusting the magnification of the photolithography apparatus to a second Mag. so that the predetermined pattern is transferred to the photoresist layer to form a

second pattern, wherein the second Mag. is not equal to the first Mag., and the first pattern and the second pattern are formed on the light-guiding channel without overlapping one another;

wherein the first pattern and the second pattern are simultaneously transferred in step (c) to the light-guiding channel on the wafer.

5. (Original) The method as claimed in claim 1, wherein the first Mag. is a positive integer or a non-positive integer.

6-9. (Cancelled)